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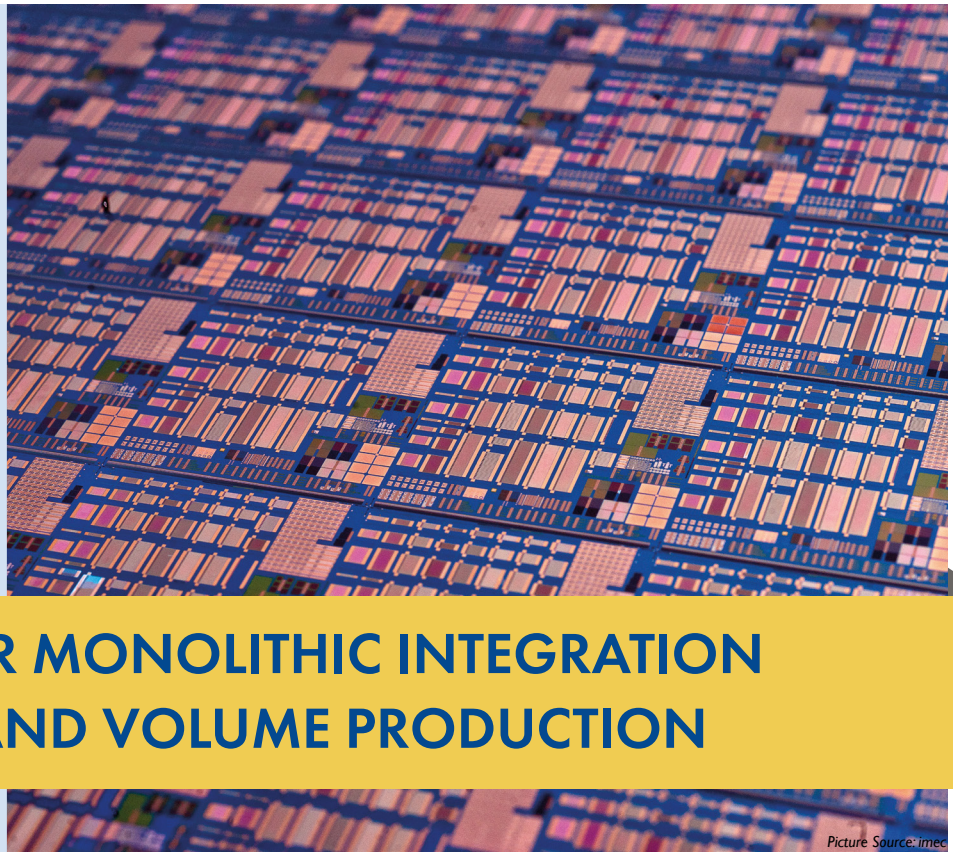


Picture Source: imec

imec GaN-IC FOR MONOLITHIC INTEGRATION PROTOTYPING AND VOLUME PRODUCTION

EUROPRACTICE-IC offers Multi-Project-Wafer and Volume Production services of imec technologies, including GaN-IC for monolithic integration of power systems.

Why EUROPRACTICE?

- Affordable and easy access to Prototyping and Small Volume Production services for academia and industry.
- MPW (Multi-Project-Wafer) runs for various technologies, including ASICs, Photonics, MEMS and GaN.
- Advanced packaging, system integration solutions and test services.

Why imec GaN-IC?

- Integrating multiple transistors on a single IC using trench isolation.
- Reducing system parasitic inductance.
- Saving package cost by packaging one instead of multiple devices.
- Working with a world-leading research and innovation hub in nanoelectronics and digital technologies headquartered in Belgium.

Technology Highlights

To unlock the full potential of GaN power electronics, imec offers a unique GaN-on-SOI process. The deep-trench isolation implemented in this process provides full isolation between power devices, drivers, control and protection circuits. This, in turn, enables the manufacturing of complex GaN ICs. In addition to accommodating smaller form factors, the close proximity of devices drastically reduces parasitic inductance, resulting in a significant switching speed enhancement.

State-of-the-art Enhancement Mode Power Devices on 200mm/8-inch Si Wafer

Today, GaN-based power devices are mainly available as discrete components which have, nonetheless, been used to push both operating frequencies and efficiencies of Switched-Mode Power Supplies (SMPS) to record levels. The technology's full potential, however, has been difficult to unlock due to difficulties in reducing the parasitic inductances, the necessity of extremely fast turn-on times, and the low Cg/Cgd ratio. Solutions using discrete GaN power devices have therefore resulted in maximum switching speeds far short of their potential values. Imec's GaN-on-SOI IC technology circumvents these limitations by allowing customers to monolithically integrate components such as half-bridge and GaN drivers onto the same die, minimizing parasitic inductance.

GaN-on-SOI Design Kit

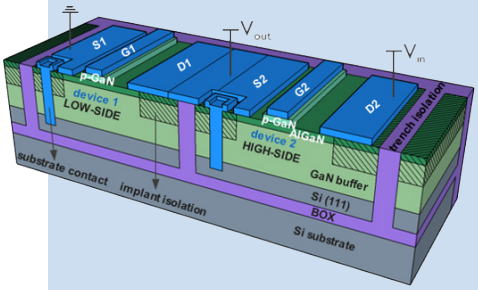
To make this technology more easily available, imec provides an extensive GaN-on-SOI Process Design Kit (PDK). This kit includes process documentation, library devices, layout guidelines for custom design, verification and models. Low-ohmic and high-ohmic resistors are provided, as well as Metal/Oxide/Metal capacitors, temperature sensors and low voltage logic devices and logic gates (invertors, NAND, NOR, RS Flip-flops,...). These enable customers to design highly integrated GaN power systems on chip. The PDK is available after signing imec's GaN-IC Design Kit License Agreement (DKLA).

Monolitic Integration Using GaN-on-SOI

Except for systems at low voltage (<50Volt), co-integration of low-side and high-side power devices is not possible using GaN-on-Si substrates :

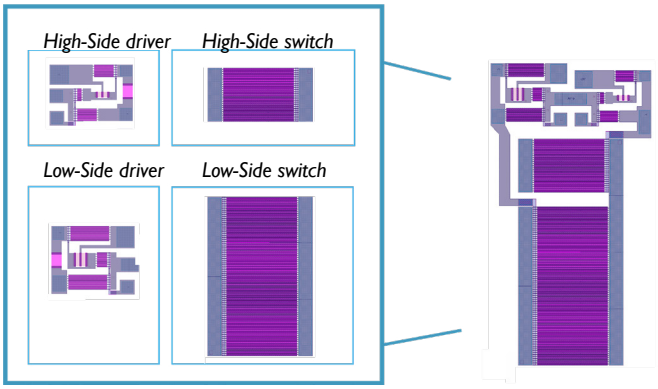
- The common Si substrate results in back-gating effects on the high-side power devices.
- The buried oxide of the SOI, the oxide-filled deep trenches and the deep Si contact effectively eliminate the back-gating effect.

To use the full potential of the fast switching speed of GaN power devices, the drivers should be co-integrated to lower the parasitic inductance. Further functionality can be added through the low-voltage logic and analog switches, the high-ohmic and low-ohmic resistors and the integrated MIM-capacitors.



Schematic cross-section of monolithically integrated half-bridge with enhancement mode low-side and high-side devices fabricated on 200 mm GaN-on-SOI with trench isolation.

Discrete components on PCB **Integrated half-bridge and driver**



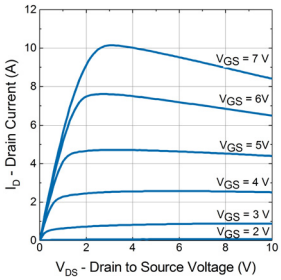
Monolithic integration of half-bridge and gate driver on imec's GaN IC platform.

Technology Details

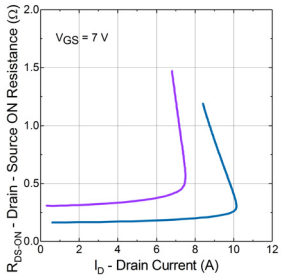
200 V e-MODE p-GaN HEMT

Datasheet Power Device with Weff = 36 mm

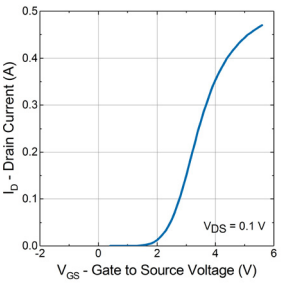
Symbol	Description	Test Conditions	MIN	TYP	MAX	UNIT
Absolute Maximum Ratings						
BV_{DS}	Drain-Source voltage				200	V
I_D	Pulsed Drain current	1 ms pulse			10	A
V_{GS}	Gate-Source voltage				7	V
ON/OFF STATE CHARACTERISTICS						
BV_{DS}	Drain-Source voltage	VGS = 0 V, ID = 1 µA/mm	200			V
I_{DSS}	Drain-Source leakage	VGS = 0 V, VDS = 200 V		0.5		µA
I_{GSS}	Gate-Source leakage	VGS = 0 V, VDS = 200 V		0.27		µA
R_{DS-ON}	Drain-Source ON resistance	VGS = 7 V, ID = 2 A		0.16		Ω
V_{TH}	Gate-Source voltage	maximum gm		2.3		V
		VDS = 0.1 V, ID = 10 µA/mm		1.3		
DYNAMIC CHARACTERISTICS						
C_{ISS}	Input capacitance	VGS = 0 V VDS = 200 V f = 1 MHz		55		pF
C_{OSS}	Output capacitance			35		pF
C_{RSS}	Reverse transfer capacitance			0.97		pF



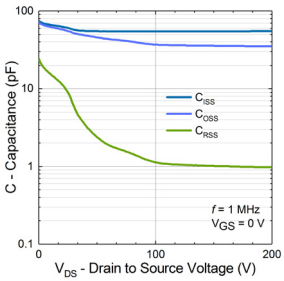
Typical IDS vs.VDS curve at T=25 °C



RDS vs. VDS(on) vs IDS at T=25 and 150 °C



Typical IDS vs.VGS curve at T=25 °C



Typical CISS , COSS and CRSS vs VDS at T=25 °C Measurements on-wafer (no packaging parasitics included).